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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
	:	Examiner: NYA
YOSHIKAZU MIYAJIMA ET AL.)	
	:	Group Art Unit: 2811
Application No.: 10/022,506)	
	:	
Filed: December 20, 2001)	
	:	
For: EXPOSURE APPARATUS, DEVICE)	
MANUFACTURING METHOD,	:	
SEMICONDUCTOR)	
MANUFACTURING FACTORY,	:	
AND EXPOSURE APPARATUS)	
MAINTENANCE METHOD		March 26, 2002

Office of Initial Patent Examination Customer Service Center Commissioner for Patents Washington, D.C. 20231

REQUEST FOR CORRECTED FILING RECEIPT

Sir:

Applicants' attorneys have received an official Filing Receipt in the above-identified application wherein an error has been noted. The Title is incorrect and should read:

--Exposure apparatus, device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method--.

A copy of the official Filing Receipt is attached with the proposed change marked in red. Issuance of a Corrected Filing Receipt with the correct data is accordingly respectfully requested.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our address given below.

Respectfully submitted,

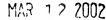
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UNITED STATES PATENT AND TRADEMARK OFFICE

COMMISSIONER FOR PATENTS

UNITED STATES PATENT AND TRADEMARK OFFICE WASHINGTON, D.C. 20231

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APPLICATION NUMBER FILING DATE **GRP ART UNIT** FIL FEE REC'D ATTY.DOCKET.NO DRAWINGS TOT CLAIMS IND CLAIMS 10/022,506 12/20/2001 2811 1502 862.C2476 33 39 8

CONFIRMATION NO. 2840

FILING RECEIPT

OC000000007385526

Date Mailed: 01/30/2002

05514 FITZPATRICK CELLA HARPER & SCINTO 30 ROCKEFELLER PLAZA NEW YORK, NY 10112

00862.023476

Receipt is acknowledged of this nonprovisional Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Customer Service Center. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Yoshikazu Miyajima, Tochiqi, JAPAN; Kazuhito Outuka, Tokyo, JAPAN; Keiji Emoto, Kanagawa, JAPAN:

Domestic Priority data as claimed by applicant

Foreign Applications

JAPAN 2000-395819 12/26/2000

If Required, Foreign Filing License Granted 01/29/2002

Projected Publication Date: 06/27/2002

Non-Publication Request: No

Early Publication Request: No

Title

Exposure, apparatus, device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method

Preliminary Class

257



LICENSE FOR FOREIGN FILING บที่บิ่ยห Title 35, United States Code, Section 184 Title 37, Code of Federal Regulations, 5.11 & 5.15

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Bib Data Sheet

CONFIRMATION NO. 2840

SERIAL NUMBER 10/022,506	FILING DATE 12/20/2001 RULE	C	257/ . 3/5	GROUP ART UNIT			ATTORNEY) DOCKET NO. 3 862 C2476			
Kazuhito Outúl Keiji Emoto, Ka ** CONTINUING DA ⁻ ** FOREIGN APPLIC		***** *****	icu:					7,500		
IF REQUIRED, FOREIGN FILING LICENSE GRANTED ** 01/29/2002										
Foreign Priority claimed 35 USC 119 (a-d) conditions wet Verified and Acknowledged Acknowledged			STATE OR COUNTRY JAPAN	SHEETS DRAWING 33		TOTAL CLAIMS 39		INDEPENDENT CLAIMS 8		
ADDRESS 05514										
TITLE Exposure apparatus, apparatus maintenan	device manufacturing m	nethod, se	emiconductor r	manufa	ecturing	factory, a	and e	xposure		
RECEIVED No.	S: Authority has been g to charge/cr for following	e/credit DEPOSIT ACCOUNT			☐ All Fees ☐ 1.16 Fees (Filing) ☐ 1.17 Fees (Processing Ext. of time) ☐ 1.18 Fees (Issue) ☐ Other ☐ Credit					